

INFORMATION DISCLOSURE STATEMENT

Applicant : Ogata et al.
App. No : 10/589,681
Filed : August 16, 2006
For : POLYMER COMPOUND,
PHOTORESIST COMPOSITION
INCLUDING THE POLYMER
COMPOUND, AND RESIST
PATTERN FORMATION METHOD
Examiner : Chu, John S Y
Art Unit : 1795
Conf No. : 9916

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 5 (five) references, of which 4 (four) are enclosed/submitted.

This Information Disclosure Statement is being filed after the mailing date of a final action or after the mailing date of a Notice of Allowance. This Statement is accompanied by the fee set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(1)

I hereby certify that each item of information contained in this Statement was first cited in any communication from a foreign Patent Office in a counterpart foreign application not more

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than 30 days prior to the filing of this Information Disclosure Statement.

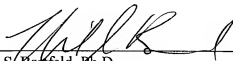
Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: _____

2/11/10

By: _____



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